14 44

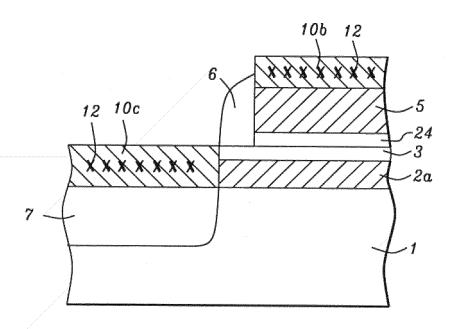


FIG. 17

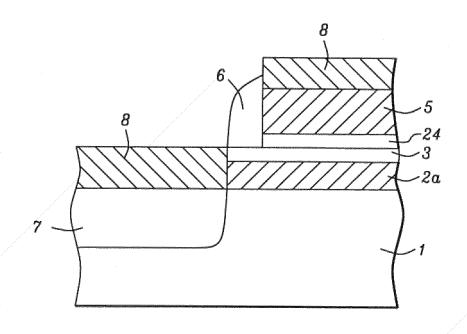


FIG. 18

2001.1531/24061.439
Chien-Chao Huang et. al.
IMPROVED COBALT SILICIDATION
PROCESS FOR SUBSTRATES WITH A
SILICON GERMANIUM LAYER
1 of 9

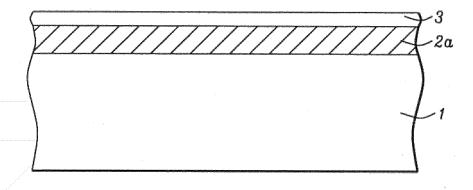


FIG. 1

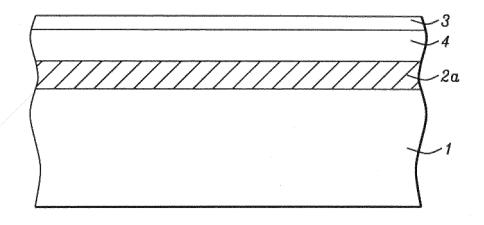
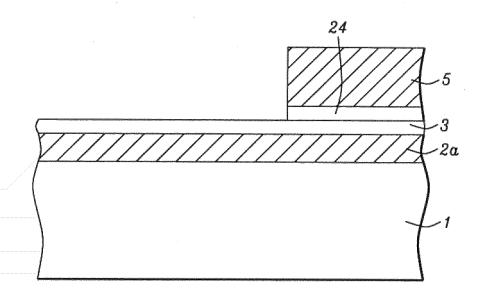


FIG. 2

4 1 6 1



*FIG.* 3

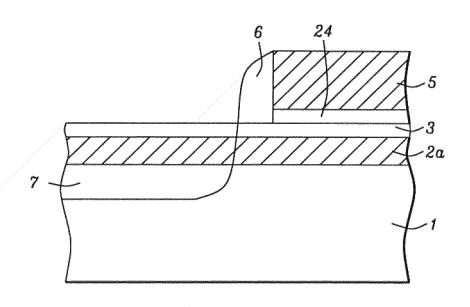


FIG. 4

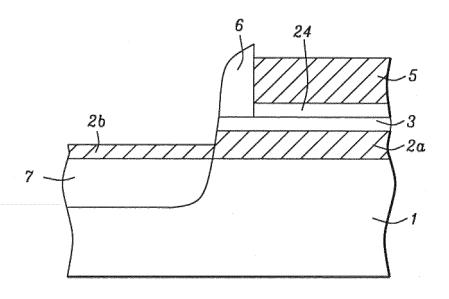


FIG. 5

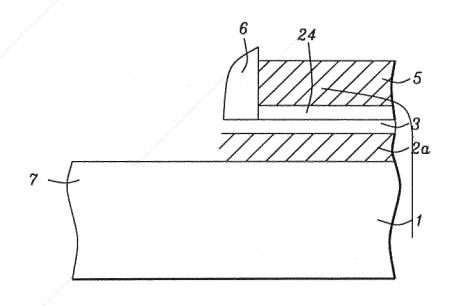
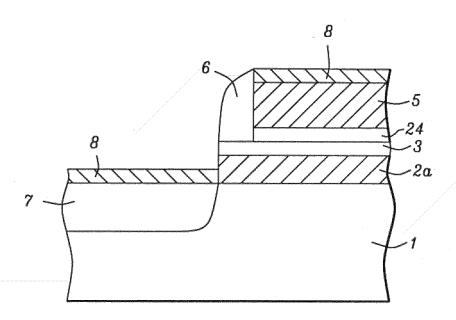


FIG. 6

2001.1531/24061.439
Chien-Chao Huang et. al.
IMPROVED COBALT SILICIDATION
PROCESS FOR SUBSTRATES WITH A
SILICON GERMANIUM LAYER
4 of 9



*FIG.* 7

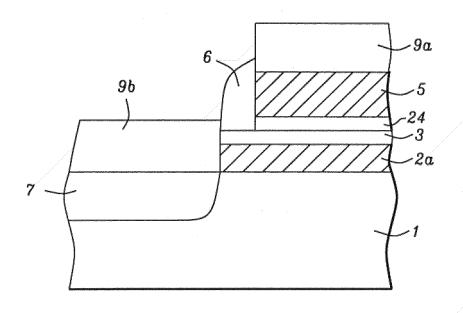


FIG. 8

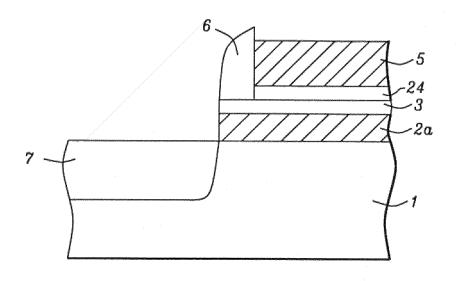


FIG. 9

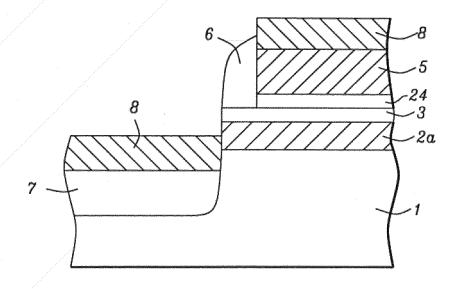


FIG. 10

6 / 22

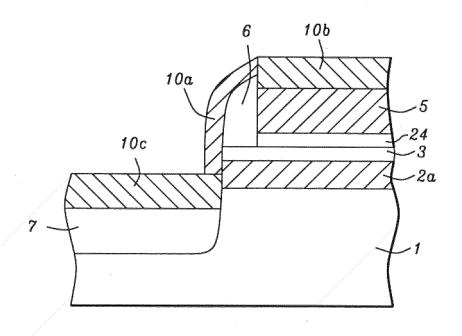


FIG. 11

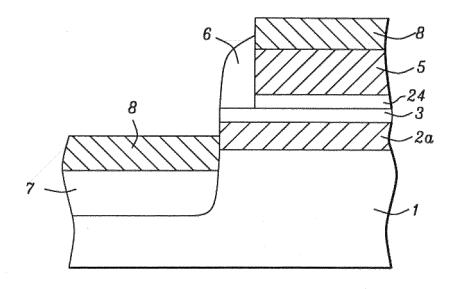


FIG. 12

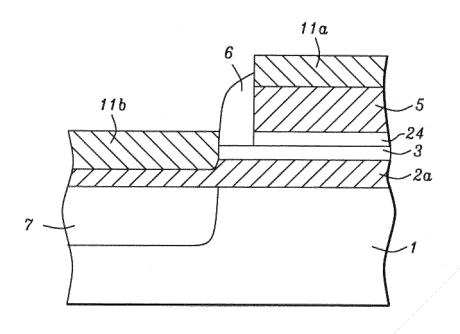


FIG. 13

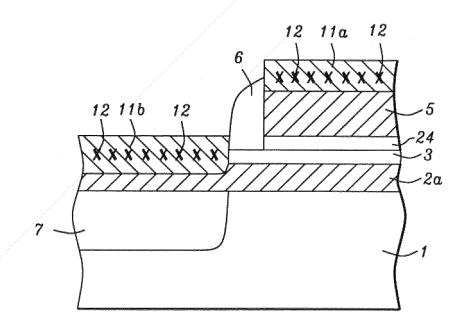


FIG. 14

\* / \* \*\*

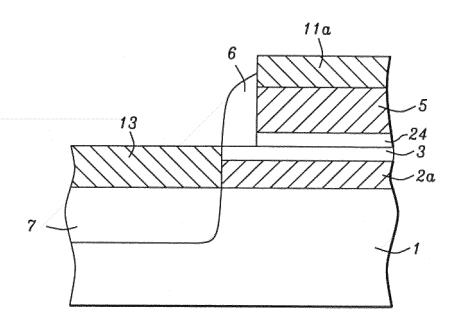


FIG. 15

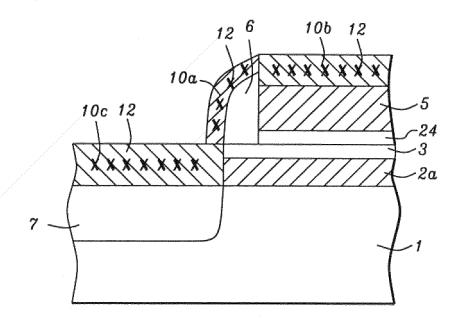


FIG. 16

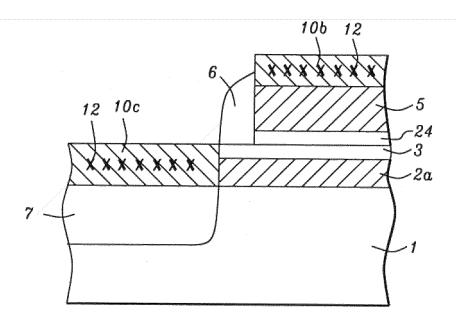


FIG. 17

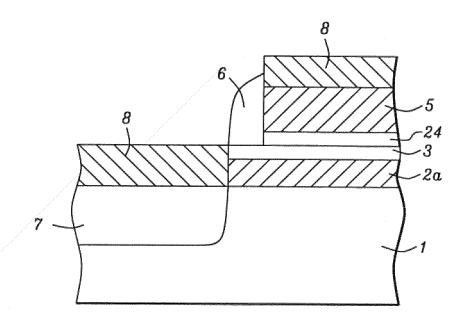


FIG. 18